課題番号 :F-17-TU-0046

利用形態 :機器利用

利用課題名(日本語) :Fe 基金属ガラスのナノインプリンティングによる磁性制御

Program Title(English) : The magnetic property of nanoimprinting Fe based metallic glass

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キーワード/Keyword : 膜加工・エッチング、Cr mask, Photolithography, RIE etching, KOH etching

1. 概要(Summary)

The shape of a magnetic material strongly affects the magnetization process. Therefore, various kinds of patterns from micrometers to nano-meters were fabricated to tailor the magnetic anisotropy and domain dynamics. Nano-imprinting of Fe-based metallic glasses is very promising, simultaneously the accurate Si die is vital to realize low cost magnetic nano-structures. Thus, the fabrication process of variety of different specification Si molds was performed in Nishizawa center.

2. 実験(Experimental)

【利用した主な装置】 両面アライナ露光装置一式、レーザ描画装置、アネルバ RIE 装置

【実験方法】

- 1. Fabricating the Cr mask with a variety of different size patterns by laser writing.
- 2. Coating the photoresist on Si wafer and then performing photolithography with UV exposure.
- 3. Removing the SiO₂ layer by reactive ion etching and the perform KOH etching to fabricate the patterns.

3. 結果と考察(Results and Discussion)

A variety of different specification Si molds are finished successfully. But the terminal structure is different because of KOH etching. And the figure 1 and 2 show their structures after photolithography and KOH etching respectively.

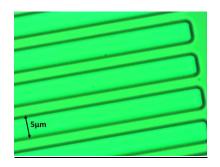


Fig. 1 Pictures of Si wafer after photolithography by optical microscope

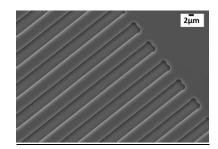


Fig. 2 Pictures of Si wafer after KOH etching by SEM

<u>4. その他・特記事項(Others)</u>

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5. 論文·学会発表(Publication/Presentation)

(1) Liang Xiaoyu, Parmanand Sharma, Hidemi Kato, International Conference on Materials and Systems for Sustainability 2017, 2017.09.30

6. 関連特許(Patent)

なし。